	Type	L #	Hits	Search Text	DBs	Time Stamp
1	IS&R	L1	1212	(427/569).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 07:53
2	IS&R	L3	265	(427/573).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 07:55
3	BRS	L4	97795	(chang$3 or increas$3 or decreas$3) same (flow adj3 rate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 07:57
4	BRS	L5	696	4 same ("SiH.sub.4" or "SiF.sub.4" or "TEOS")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 07:58
5	BRS	L6	11	5 same (nozzle or nozzles)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 08:46

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L7	982	(first adj (flow adj rate)) same (second adj (flow adj rate))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 08:47
7	BRS	L8	8	7 and (breakdown adj3 voltage$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 08:54
8	BRS	L9	982	7 same (second or seconds)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 08:54
9	BRS	L10	28	9 same (nozzle or nozzles)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 09:07
10	IS&R	L12	352	(427/574).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 09:15

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	862	(first adj flow adj rate) with (second adj flow adj rate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 13:16
2	BRS	L2	52	1 with after	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 13:22
3	BRS	L3	2	2 with plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/06 13:26

(second! or another or additional) near 2
(nozzle or inject or port) near 4
((reactant near 2 gas or reactant) or
("Si H sub x" or "Si F sub 4" or
TEOS).

US-PAT-NO: 6120606

DOCUMENT-IDENTIFIER: US 6120606 A

TITLE: Gas vent system for a vacuum chamber

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a second line connected **after** said gas regulator, said second line being
connected in parallel with said first line, said second line having a second
metering valve and an in-line valve in series, **after** said first line starts to
vent said gas into said vacuum chamber, said second line allowing said gas to
pass through into said vacuum chamber in a **second flow rate** higher than said
first flow rate for increasing a venting rate of said vacuum chamber by opening
said first line and said second line at a same time;

a second line connected **after** said gas regulator, said second line being
connected in parallel with said first line, said second line having a second
metering valve and an in-line valve in series, **after** said first line starts to
vent said gas into said vacuum chamber, said second line allowing said gas to
pass through into said vacuum chamber in a **second flow rate** higher than said
first flow rate for increasing a venting rate of said vacuum chamber by opening
said first line and said second line at a same time;